Preliminary development of MCP simulation

Han Miao, Kaile Wen, Baojun Yan

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Principle





- When incident particle hit the emission material, secondary electrons will be possible to be activated and escaped to the channel
- Secondary electrons will be accelerated as a high voltage are applied to the ends of the channel
- Secondary electrons hit the surface of emission material and more secondary electrons will be created.



- Assuming that this process happens at the surface of the hole in MCP;
- Incident electrons will be transformed to secondary electrons or absorbed by MCP material once they hit the inner surface;
- Furman model is used to sample the secondary electrons emmitted from material



- Secondary electrons are divided to three kinds:
 - elestic backscattered secondary electrons
 - ➢ rediffused secondary electrons
 - ➤ true secondary electrons
- When the electron hit the surface vertically, the secondary electron yield is obtained experimentally
- If there's an angle between incident and normal direction, the yield can be obtained by multiplying a coefficient:

$$P(\theta) = P(0) \cdot e^{-\frac{L}{\lambda}(1 - \cos\theta)}$$

P(0) – yield when electrons hit vertically

$$\frac{L}{\lambda}$$
 - coefficient got from experiment



- The average yields of secondary electrons can be got from the method above
- Then we sample Gaussian distributions whose mean value and standard deviation are both the average yields to got the yields in this certain event.
- The process corresponding the highest yield will happen in this certain event
- The number of electrons is obtained by sampling a Poisson distribution whose mean value is the average yield.



• Angular distribution of secondary electrons:

 $\frac{dP}{d\theta} = Ae^{-\frac{c}{\cos\theta}}$ $A - normalization \ coefficient$ $c - coefficient \ got \ by \ experiment$

- Energy spectrum of secondary electrons:
 - elestic backscattered secondary electrons

$$f(E) = \frac{2exp[\frac{(E - E_p)^2}{2\sigma_e^2}]}{\sigma_e \cdot erf(\frac{E_p}{\sqrt{2}\sigma_e})}$$
$$E_p - incident \ energy$$

 σ_e – standard deviation of emission spectrum



rediffused secondary electrons:

$$f(E) = \frac{(q+1)E^q}{E_p^{q+1}}$$

 E_p – incident energy q – coefficient by fitting

true secondary electrons:

$$f(E) = E^{\rho_n - 1} e^{\frac{-E}{\kappa_n}}$$

$$\rho_n, \kappa_n - coefficient by fitting$$

Preliminary development

Detector Construction

- Only one channel is taken into simulation for now
- The parameters of MCP are got from manual provided by factory:

Parameter	Value
Thickness of MCP	0.38 mm
Radius of MCP	3e-2 mm
Radius of channel	3e-3 mm
Rotation of channel	6 degree
High voltage	500 V





- 100 eV electrons are set to be the particle source
- When the yields of secondary electrons are fixed to be 2, the process works properly
- If the yields are got from sampling, secondary electrons cannot be created properly



We are trying our best to fix this problem

Summary



- Furman model has been used in our simulation work
- Detector model has been successfully constructed in program
- Secondary electron emission process still has some problems and we are trying to figure it out

Next work



- Solve the problem we meet when implementing new process
- Construct the complete geometry of MCP
- Calculate the eletric field in the channel
- Get the response of MCP

Thank you !